## Alexander A Shklyaev

List of Publications by Year in descending order

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279798 315739 120 1,833 23 38 citations h-index g-index papers 120 120 120 802 docs citations citing authors all docs times ranked

#	Article	IF	Citations
1	Interdisk spacing effect on resonant properties of Ge disk lattices on Si substrates. Scientific Reports, 2022, 12, 8123.	3.3	4
2	The Modification of Optical Properties of the Surfaces by the Glancing Angle Deposition Technique. Siberian Journal of Physics, 2021, 16, 91-100.	0.3	O
3	Electron Spin Resonance in Heterostructures with Ring Molecules of GeSi Quantum Dots. JETP Letters, 2021, 113, 52-56.	1.4	O
4	Crossing and anticrossing of 1D subbands in a quantum point contact with in-plane side gates. Applied Physics Letters, 2021, $118$ , .	3.3	5
5	Electrostatic actuation and charge sensing in piezoelectric nanomechanical resonators with a two-dimensional electron gas. Applied Physics Letters, 2021, 118, .	3.3	4
6	Broadband Antireflection Coatings Made of Resonant Submicron- and Micron-Sized SiGe Particles Grown on Si Substrates. IEEE Photonics Journal, 2021, 13, 1-12.	2.0	8
7	BROADBAND ANTIREFLECTION COATING COMPOSED OF RESONANT SIGE PARTICLES OF SUBWAVELENGTH SIZE. Avtometriya, 2021, 57, 58-69.	0.0	O
8	Broadband Antireflection Coatings Composed of Subwavelength-Sized SiGe Particles. Optoelectronics, Instrumentation and Data Processing, 2021, 57, 494-504.	0.6	2
9	Atomic structure of high Miller index Si(47 35 7) surface. Surface Science, 2020, 693, 121549.	1.9	4
10	Effect of deposition conditions on the thermal stability of Ge layers on SiO2 and their dewetting behavior. Thin Solid Films, 2020, 693, 137681.	1.8	8
11	Dewetting behavior of Ge layers on SiO2 under annealing. Scientific Reports, 2020, 10, 13759.	3.3	12
12	Low-temperature dissipation and its persistent photoinduced change in AlGaAs/GaAs-based nanomechanical resonators. Applied Physics Letters, 2020, 116, .	3.3	3
13	Formation of submicron- and micron-sized SiGe and Ge particles on Si substrates using dewetting. Journal of Physics: Conference Series, 2020, 1461, 012160.	0.4	O
14	Double-Channel Electron Transport in Suspended Quantum Point Contacts with in-Plane Side Gates. Semiconductors, 2020, 54, 1605-1610.	0.5	4
15	Universal building block for (1 $1$ 0)-family silicon and germanium surfaces. Applied Surface Science, 2019, 494, 46-50.	6.1	11
16	Nanoscale characterization of photonic metasurface made of lens-like SiGe Mie-resonators formed on Si (100) substrate. Journal of Applied Physics, 2019, 126, 123102.	2.5	8
17	On-Chip Piezoelectric Actuation of Nanomechanical Resonators Containing a Two-Dimensional Electron Gas. JETP Letters, 2019, 109, 261-265.	1.4	2
18	Suspended quantum point contact with triple channel selectively driven by side gates. Applied Physics Letters, 2019, 115, .	3.3	6

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19	Electromigration effect on the surface morphology during the Ge deposition on Si(1â€⁻1â€⁻1) at high temperatures. Applied Surface Science, 2019, 465, 10-14.	6.1	12
20	Lateral-electric-field-induced spin polarization in a suspended GaAs quantum point contact. Applied Physics Letters, 2018, $112$ , .	3.3	17
21	Raman and photoluminescence spectroscopy of SiGe layer evolution on Si(100) induced by dewetting. Journal of Applied Physics, 2018, 123, .	2.5	26
22	Electrically controlled spin polarization in suspended GaAs quantum point contacts. Journal of Physics: Conference Series, 2018, 1124, 061001.	0.4	0
23	The observation of the Aharonov-Bohm effect in suspended semiconductor ring interferometers. Journal of Physics: Conference Series, 2018, 964, 012008.	0.4	2
24	Shapes of the Micron-Sized SiGe Islands Grown on Si(100) in Dewetting Conditions. , 2018, , .		0
25	Kelvin force and Raman microscopies of flat SiGe structures with different compositions grown on Si(111) at high temperatures. Materials Science in Semiconductor Processing, 2018, 83, 107-114.	4.0	2
26	Surface Morphologies Obtained by Ge Deposition on Bare and Oxidized Silicon Surfaces at Different Temperatures., 2017,, 325-344.		0
27	Submicron- and micron-sized SiGe island formation on Si(100) by dewetting. Thin Solid Films, 2017, 642, 345-351.	1.8	14
28	Formation and study of p–i–n structures based on two-phase hydrogenated silicon with a germanium layer in the i-type region. Semiconductors, 2017, 51, 1370-1376.	0.5	6
29	Photonic metasurface made of array of lens-like SiGe Mie resonators formed on (100) Si substrate via dewetting. Applied Physics Express, 2017, 10, 125501.	2.4	16
30	Critical conditions for SiGe island formation during Ge deposition on Si(100) at high temperatures. Materials Science in Semiconductor Processing, 2017, 57, 18-23.	4.0	17
31	Electromechanical coupling in suspended nanomechanical resonators with a two-dimensional electron gas. Journal of Physics: Conference Series, 2017, 864, 012043.	0.4	0
32	SURFACE MORPHOLOGY OF GERMANIUM LAYERS ON SILICON SURFACES AT HIGH TEMPERATURES. , 2017, , 410-413.		1
33	Hydrogenated amorphous silicon based p-i-n structures with Si and Ge nanocrystals in i-layers. , 2016, ,		0
34	Photoconductive gain and quantum efficiency of remotely doped Ge/Si quantum dot photodetectors. Materials Research Express, 2016, 3, 105032.	1.6	20
35	Raman studies of phase and atomic compositions of GeSi nanosystems after pulsed annealing. Optoelectronics, Instrumentation and Data Processing, 2016, 52, 496-500.	0.6	4
36	Surface Morphology Transformation Under High-Temperature Annealing of Ge Layers Deposited on Si(100). Nanoscale Research Letters, 2016, 11, 366.	5.7	9

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37	Piezoelectric Electromechanical Coupling in Nanomechanical Resonators with a Two-Dimensional Electron Gas. Physical Review Letters, 2016, 117, 017702.	7.8	16
38	Formation of lateral nanowires by Ge deposition on Si(111) at high temperatures. Journal of Crystal Growth, 2016, 441, 84-88.	1.5	7
39	Kinetics and thermodynamics of Si(111) surface nitridation in ammonia. Journal of Crystal Growth, 2016, 441, 12-17.	1.5	9
40	Ge deposition on Si(1 $0$ $0$ ) in the conditions close to dynamic equilibrium between islands growth and their decay. Applied Surface Science, 2016, 360, 1023-1029.	6.1	21
41	Nucleation and growth of ordered groups of SiGe quantum dots. Semiconductors, 2015, 49, 149-153.	0.5	6
42	Strain-induced Ge segregation on Si at high temperatures. Journal of Crystal Growth, 2015, 413, 94-99.	1.5	15
43	Structure and optical properties of Si and SiGe layers grown on SiO2 by chemical vapor deposition. Thin Solid Films, 2015, 579, 131-135.	1.8	14
44	Actuation and transduction of resonant vibrations in GaAs/AlGaAs-based nanoelectromechanical systems containing two-dimensional electron gas. Applied Physics Letters, 2015, 106, 183110.	3.3	15
45	Properties of three-dimensional structures prepared by Ge dewetting from ${ m Si}(111)$ at high temperatures. Journal of Applied Physics, 2015, 117, .	2.5	23
46	Mechanisms of surface morphology formation during Ge growth on Si(100) at high temperatures. , 2015, , .		0
47	Super-dense array of Ge quantum dots grown on Si(100) by low-temperature molecular beam epitaxy. Journal of Applied Physics, 2014, 115, 144306.	2.5	17
48	Surface morphology of Ge layers epitaxially grown on bare and oxidized Si(001) and Si(111) substrates. Surface Science, 2014, 625, 50-56.	1.9	26
49	Highly Directive and Broadband Radiation From Photonic Crystals With Partially Disordered Cavities Arrays. Journal of Lightwave Technology, 2014, 32, 4879-4883.	4.6	5
50	Surface morphology formation of Ge layers on Si(111) under high-temperature annealing. , 2014, , .		0
51	Impact ionization of excitons in Ge/Si structures with Ge quantum dots grown on the oxidized Si(100) surfaces. Journal of Applied Physics, 2014, 115, 203702.	2.5	5
52	Structure and stability of Ge cluster on Si(111) surface in the presence of Bi surfactant. Surface Science, 2013, 617, 68-72.	1.9	6
53	Formation and structural features of silicon quantum dots in germanium. Optoelectronics, Instrumentation and Data Processing, 2013, 49, 434-439.	0.6	3
54	Surface morphology of Si layers grown on SiO2. Applied Surface Science, 2013, 267, 40-44.	6.1	4

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55	Resonant photoluminescence of Si layers grown on SiO2. Optics Communications, 2013, 286, 228-232.	2.1	3
56	Shape of epitaxial Ge islands on Si(100) surfaces. , 2013, , .		1
57	Epitaxial Ge Growth on Si(111) Covered with Ultrathin SiO <sub>2</sub> Films. Journal of Surface Engineered Materials and Advanced Technology, 2013, 03, 195-204.	0.2	8
58	Excitation Dependence of Photoluminescence in the 1.5-1.6 $\hat{l}$ /4m Wavelength Region from Grown Dislocation-Rich Si Layers. Physics Procedia, 2012, 32, 117-126.	1.2	1
59	Luminescence and deep-level transient spectroscopy of grown dislocation-rich Si layers. AIP Advances, 2012, 2, 032152.	1.3	6
60	Electroluminescence of dislocation-rich Si layers grown using oxidized Si surfaces. Journal Physics D: Applied Physics, 2011, 44, 025402.	2.8	15
61	Formation of Ge clusters at a Si(111)-Bi- \$sqrt 3 imes sqrt 3\$ surface. JETP Letters, 2011, 93, 661-666.	1.4	2
62	Effect of dislocations on the shape of islands during silicon growth on the oxidized Si(111) surface. JETP Letters, 2011, 94, 442-445.	1.4	5
63	Stability of the (0001) surface of the Bi2Se3 topological insulator. JETP Letters, 2011, 94, 465-468.	1.4	20
64	Influence of triplet states on the spectrum of collective spin-polaron excitations in a 2D kondo lattice. Physics of the Solid State, 2011, 53, 1997-2000.	0.6	3
65	Quantum fluctuations in a two-dimensional antiferromagnet with four-spin interaction of cubic symmetry. Physics of the Solid State, 2011, 53, 2061-2066.	0.6	0
66	The effect of spin correlations on a superconducting phase of the spin polarons in 2D Kondo lattice. Journal of Physics: Conference Series, 2010, 200, 012217.	0.4	1
67	1.5–1.6 μm photoluminescence of silicon layers with a high density of lattice defects. Semiconductors, 2010, 44, 432-437.	0.5	12
68	Excitation-dependent blue shift of photoluminescence peak in 1.5& $\pm$ x2013;1.6 & $\pm$ x00B5;m wavelength region from dislocation-rich Si layers. , 2010, , .		1
69	Defect-related light emission in the 1.4–1.7â€,μm range from Si layers at room temperature. Journal of Applied Physics, 2009, 105, .	2.5	20
70	Photoluminescence study of energy levels in Ge quantum dots in Si., 2009,,.		1
71	Defect-related luminescence from nanostructured Si layers in the 1.5-1.6 $\hat{l}^1\!\!/\!4$ m wavelength region. Proceedings of SPIE, 2009, , .	0.8	0
72	Spherical aberration corrected STEM studies of Ge nanodots grown on Si(001) surfaces with an ultrathin SiO2 coverage. Applied Surface Science, 2008, 254, 7569-7572.	6.1	26

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73	Characterization of semiconductor nanostructures formed by using ultrathin Si oxide technology. Applied Surface Science, 2008, 255, 669-671.	6.1	5
74	Opto-Electronic Properties of Ge and Si Related Nanostructures on Ultrathin Si Oxide Covered Si Surfaces. Materials Research Society Symposia Proceedings, 2008, 1145, 1.	0.1	0
75	Title is missing!. Physics-Uspekhi, 2008, 51, 133.	2.2	69
76	Cs-corrected STEM studies of Ge nanodots grown on slightly oxidized Si(001) surfaces. Microscopy and Microanalysis, 2008, 14, 170-171.	0.4	2
77	Influence of growth and annealing conditions on photoluminescence of Ge/Si layers grown on oxidized Si surfaces. Journal of Physics Condensed Matter, 2007, 19, 136004.	1.8	26
78	Photoluminescence of Si layers grown on oxidized Si surfaces. Journal of Applied Physics, 2007, 101, 033532.	2.5	26
79	Photoluminescence of Geâ^•Si structures grown on oxidized Si surfaces. Applied Physics Letters, 2006, 88, 121919.	3.3	29
80	Title is missing!. Physics-Uspekhi, 2006, 49, 887.	2.2	4
81	Nanostructures on oxidized Si surfaces fabricated with the scanning tunneling microscope tip under electron-beam irradiation. Journal of Vacuum Science & Technology B, 2006, 24, 739.	1.3	5
82	Electrical transport in ultrathin Cs layers on Si(001). Physical Review B, 2005, 72, .	3.2	2
83	Local structure of Ge/Si nanostructures: Uniqueness of XAFS spectroscopy. Nuclear Instruments & Methods in Physics Research B, 2003, 199, 174-178.	1.4	6
84	Surface morphology of three-dimensional Si islands on Si(001) surfaces. Surface Science, 2003, 541, 234-241.	1.9	7
85	Visible photoluminescence of Ge dots embedded in Si/SiO2 matrices. Applied Physics Letters, 2002, 80, 1432-1434.	3.3	34
86	Effect of the interface on the local structure of Ge–Si nanostructures. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2002, 20, 1116-1119.	2.1	11
87	Observation of oscillating behavior in the reflectance difference spectra of oxidized Si(001) surfaces. Journal of Applied Physics, 2002, 91, 3637-3643.	2.5	19
88	Effect of interfaces on quantum confinement in Ge dots grown on Si surfaces with a SiO2 coverage. Surface Science, 2002, 514, 19-26.	1.9	61
89	Optical Anisotropy of Oxidized Si(001) Surfaces and Its Oscillation in the Layer-By-Layer Oxidation Process. Physical Review Letters, 2001, 87, 037403.	7.8	49
90	Continuous transfer of Ge by the tip of a scanning tunneling microscope for formation of lines. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2001, 19, 103.	1.6	9

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91	Electron-beam Initiated Transfer of Ge from Ge Islands on SiO2Surfaces to the Tip of a Scanning Tunneling Microscope. Japanese Journal of Applied Physics, 2001, 40, 3370-3374.	1.5	6
92	Local structure of Ge nanoislands on Si(111) surfaces with a SiO2 coverage. Applied Physics Letters, 2001, 78, 2563-2565.	3.3	47
93	Three-dimensional Si islands on Si(001) surfaces. Physical Review B, 2001, 65, .	3.2	50
94	Observation and nucleation control of Genanoislands on Si(111) surfaces using scanning reflection electron microscopy. Journal of Electron Microscopy, 2000, 49, 217-223.	0.9	5
95	Kinetics of tip-induced island growth on $Si(111)$ with a scanning tunneling microscope. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2000, 18, 2339.	1.6	5
96	Formation of Ge nanoislands using a scanning tunneling microscope. Journal of Applied Physics, 2000, 88, 1397-1400.	2.5	13
97	High-density ultrasmall epitaxial Ge islands on Si(111) surfaces with aSiO2coverage. Physical Review B, 2000, 62, 1540-1543.	3.2	166
98	Effect of tunneling current on the growth of silicon islands on Si(111) surfaces with a scanning tunneling microscope. Surface Science, 2000, 447, 149-155.	1.9	9
99	Formation of three-dimensional Si islands on Si(111) with a scanning tunneling microscope. Applied Physics Letters, 1999, 74, 2140-2142.	3.3	17
100	Instability of 2D Ge layer near the transition to 3D islands on Si (111). Thin Solid Films, 1999, 343-344, 532-536.	1.8	6
101	Critical oxide cluster size on Si(111). Surface Science, 1999, 423, 61-69.	1.9	8
102	Ge islands on $Si(111)$ at coverages near the transition from two-dimensional to three-dimensional growth. Surface Science, 1998, 416, 192-199.	1.9	48
103	Nanometer-scale germanium islands on $Si(111)$ surface windows formed in an ultrathin silicon dioxide film. Applied Physics Letters, 1998, 72, 320-322.	3.3	40
104	Instability of two-dimensional layers in the Stranski-Krastanov growth mode of Ge on Si(111). Physical Review B, 1998, 58, 15647-15651.	3.2	37
105	Interaction of O2 and N2O with Si During the Early Stages of Oxide Formation. , 1998, , 277-287.		3
106	Initial reactive sticking coefficient of O2 on Si(111)-7 $\tilde{A}-7$ at elevated temperatures. Surface Science, 1996, 351, 64-74.	1.9	24
107	Kinetics of initial oxidation of the Si(111)-7 $\tilde{A}$ — 7 surface near the critical conditions. Surface Science, 1996, 357-358, 729-732.	1.9	4
108	Influence of growth conditions on subsequent submonolayer oxide decomposition on Si(111). Physical Review B, 1996, 54, 10890-10895.	3.2	14

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109	Plasma-enhanced reactively evaporated deposition of SiO2 films. Applied Surface Science, 1995, 89, 49-55.	6.1	4
110	Branching of Critical Conditions for Si(111)-(7×7) Oxidation. Physical Review Letters, 1995, 75, 272-275.	7.8	23
111	Monosilane adsorption and initial growth stages of silicon layers on the (100) and oxidized silicon surfaces. Surface Science, 1992, 275, 433-442.	1.9	15
112	Effect of hydrogen on hot electron energy relaxation in SiO2 and Si3N4 films. Thin Solid Films, 1992, 221, 160-165.	1.8	5
113	Charge Transport in MOS-Structures with Low-Temperature Silicon Dioxide Films. Physica Status Solidi A, 1991, 125, 387-396.	1.7	2
114	Initial stages of the interaction of nitrous oxide and oxygen with the (100) silicon surface under low pressures. Reactivity of Solids, 1989, 7, 1-18.	0.3	16
115	Deposition of silica films by the oxidation of silane in oxygen II: The calculation of growth rates in the tube reactor. Thin Solid Films, 1981, 76, 61-68.	1.8	6
116	Leed studies of vicinal surfaces of silicon. Surface Science, 1979, 82, 445-452.	1.9	110
117	Phase transitions on clean Si(110) surfaces. Surface Science, 1977, 67, 581-588.	1.9	109
118	LEED studies of vicinal surfaces of germanium. Surface Science, 1977, 69, 205-217.	1.9	53
119	LEED investigation of germanium surfaces cleaned by sublimation of sulphide films; structural transitions on clean $Ge(110)$ surface. Surface Science, 1977, 64, 224-236.	1.9	80
120	Structural Changes in Nanometer-Thick Silicon-on-Insulator Films During High-Temperature Annealing. Semiconductors, 0, , .	0.5	O